Fast online monitoring of mechanical stress in mass processing of semiconductor wafers for photovoltaic applications

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Technical Task

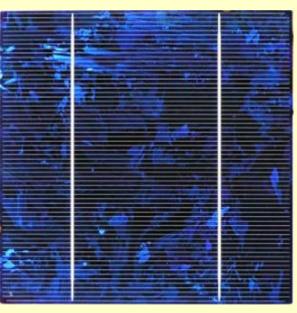
The non-destructive testing method is demanded by the photovoltaic industry to detect microcracks and critical residual stress locations within large-format ultrathin wafer in less than 1 second. The method is to be integrated into the production line to reject cracked wafers from processing.

- Wafer format
- Spatial resolution
- Operation speed
- Undetected error probability
- Locally-resolved measurements
- Wafer types
- Specific conditions

160 x 160 x 0.32 mm 100 micron < 1 s 0

Yes

Polycrystalline with polished, rough and metallized surfaces Persistent operation in fab environment





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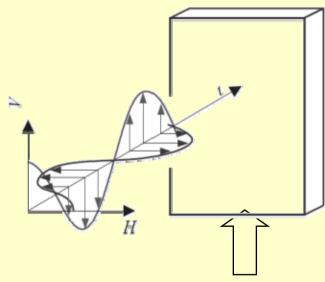


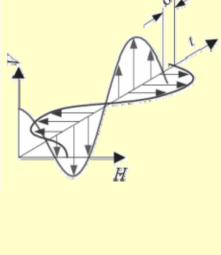
Principle

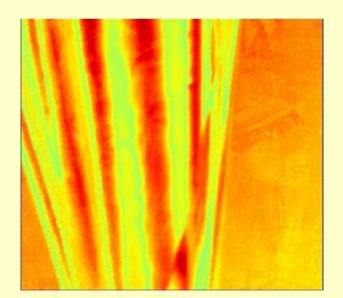


Stress-Induced Birefringence

- V Vertically polarized
- δ Birefringent retardation







Mechanical Force

Image of stress-induced birefringence in plastic



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Measuring Stress-Induced Birefringence by Heterodyne Interferometry

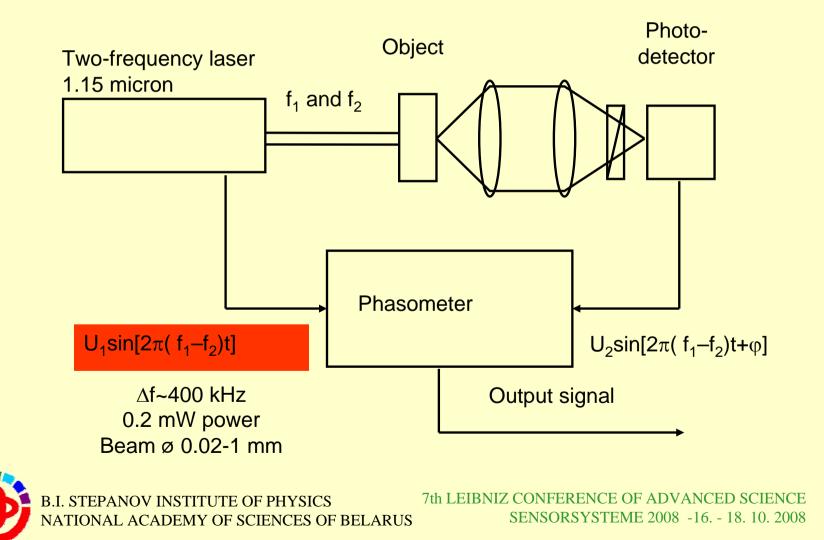
Advantages

- Measuring optical phase at radio frequency
- Ultimate accuracy, ~1degree
- High stability and good signal/noise ratio

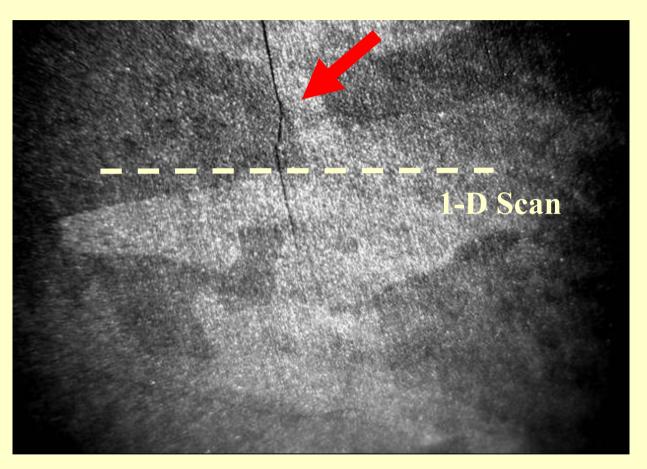




Optical Setup (Transmission)





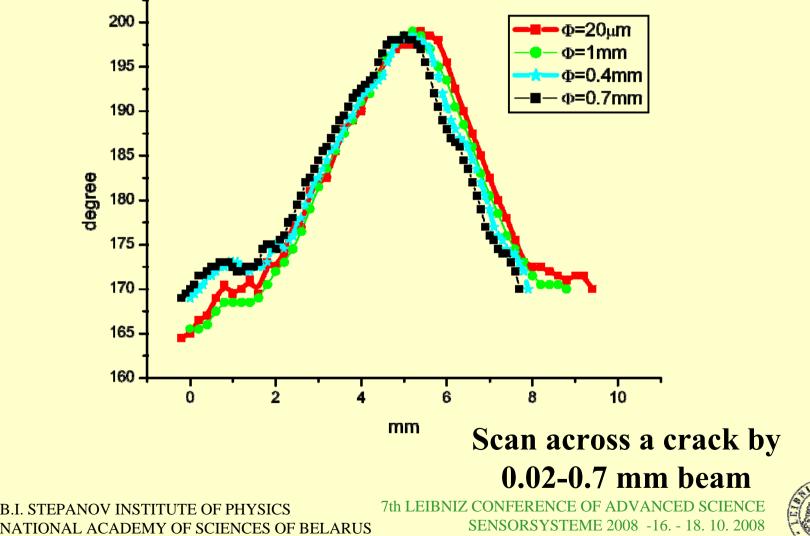


Hand-made crack

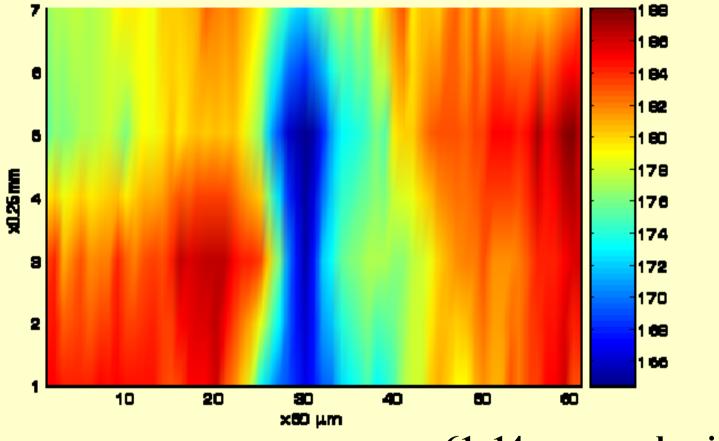


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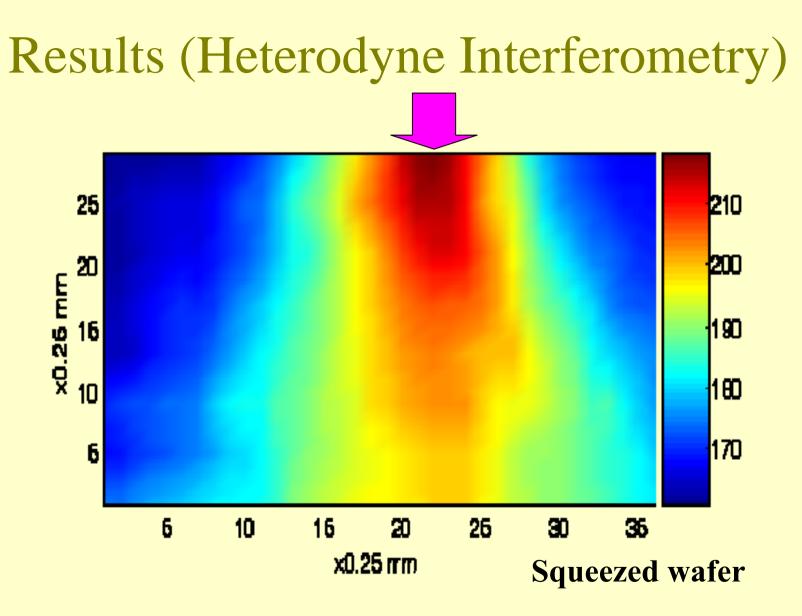


61x14 measured points



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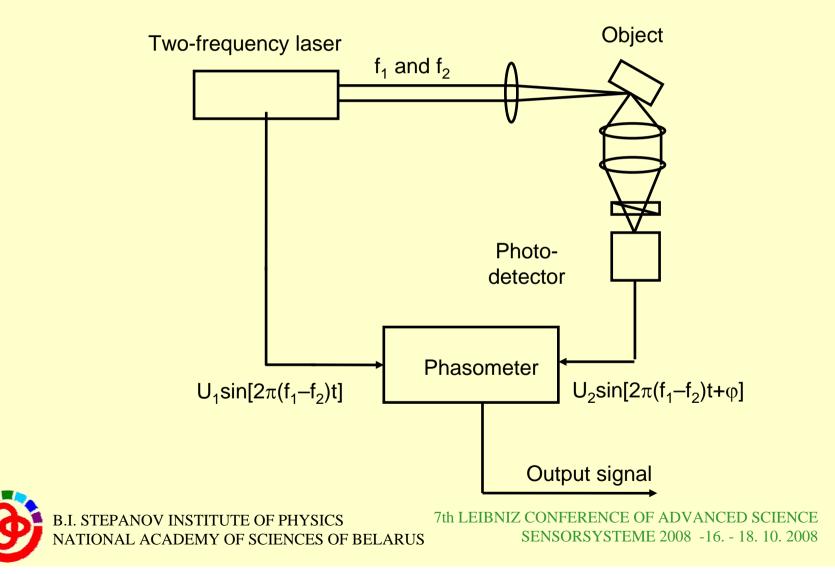




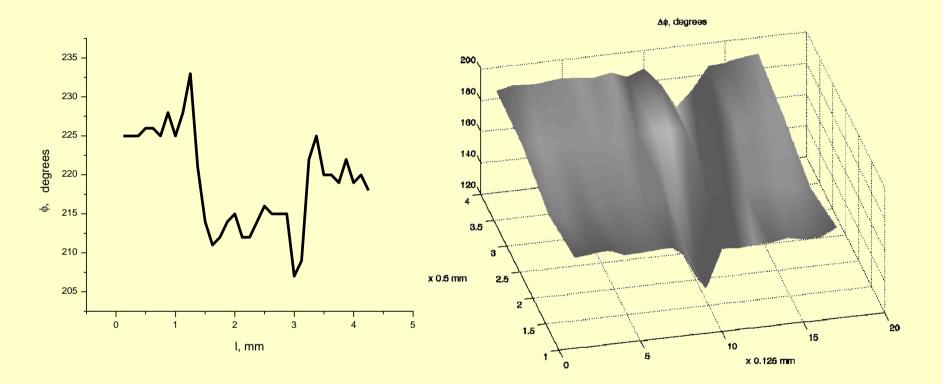
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Optical Setup (Reflection)







21x4 measured points



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Full-Field Polarizing Interferoscope

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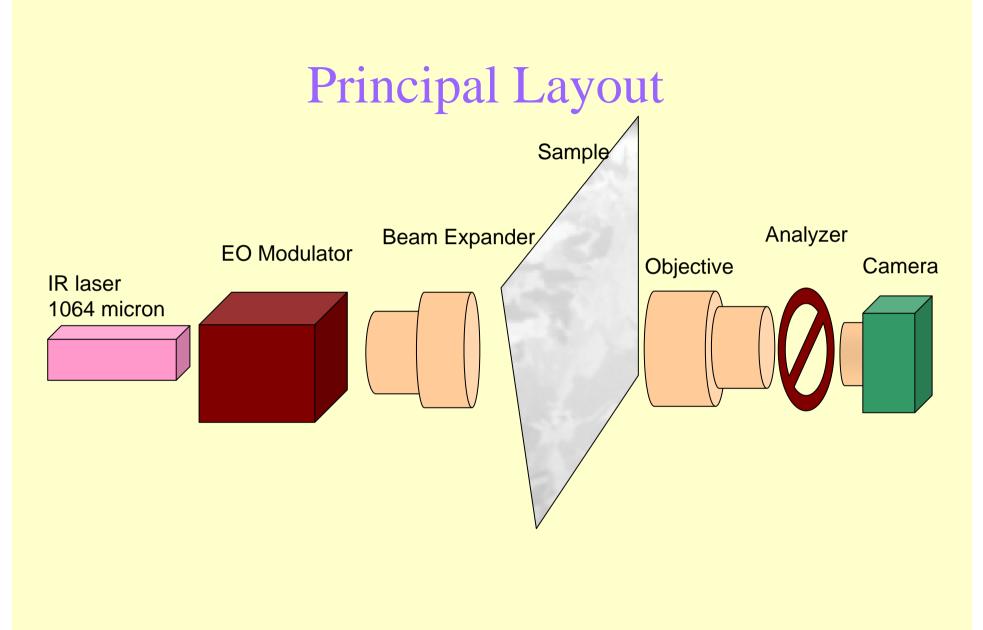
•	Wafer format	160 x 160 x 0.32 mm

- Spatial resolution 100 micron
- Operation speed < 1 s
- Undetected error probability
- Locally-resolved measurements Yes
- Wafer types Polycrystalline with polished, rough and metallized surfaces
 Specific conditions Persistent operation in fab environment



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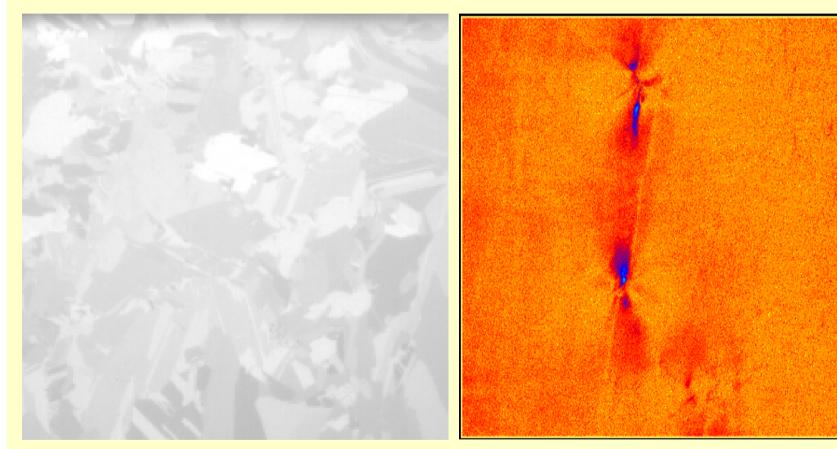




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Results



Poly-Si wafer

Processed phase image with microcrack detectable



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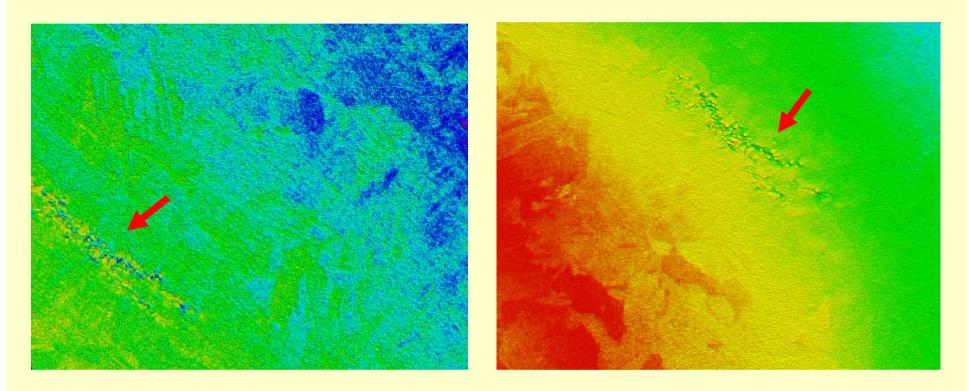
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0.05

0.45

Results



Processed phase images with microcrack detectable

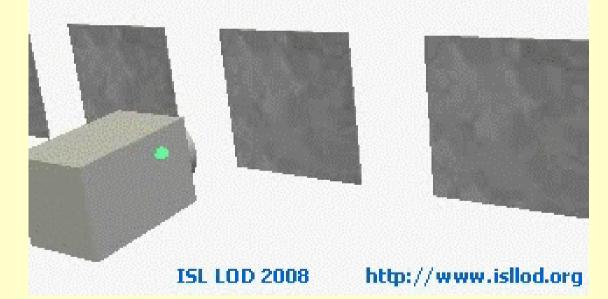


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In-situ Implementation of the Method

In-situ residual stress & microcrack control of Si wafers



Please, wait for the animation



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Conclusion

Major Results

• Feasibility of full-filed imaging of stress-induced birefringence in largeformat ultra thin poly Si wafers has been demonstrated in in transmitted and reflected light

Advantages

- High accuracy and sensitivity
- High noise immunity
- Fast measurement time
- Large field of view

Applications in photovoltaic industry

- On-line quality control of solar cells manufacturing
- Off-line solar cell characterization for improvement of production technology

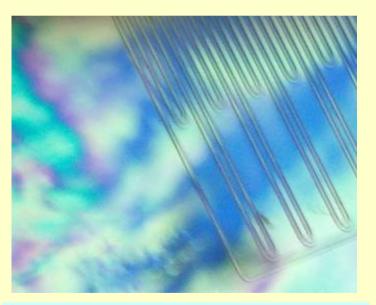


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Other Applications

3D polarization sensitive imaging by Digital Microscopy Optical Tomography for characterization of various industrial products



Stresses in plastic microfluidic component

Technology can be customized for characterization of bulk MEMS components, ceramic and glass sensors, car windows



Stresses in MEMS part



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Acknowledgements

We are grateful to Prof. B. Whilhelmi from Jena for productive discussions, support and invitation to the conference.



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Thank you for your kind attention!



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